

Nuclear Engineering Seminar

Dr. Steven Shannon

Professor & Director of Graduate Programs, North Carolina State University

Wednesday, February 14, 2024 3:30pm | PHYS 112

Ion-material interactions for critical etch processes

Abstract

Plasma assisted materials processing plays a major role in semiconductor manufacturing. Plasma sources are used in over 25% of the 500+ steps it takes to fabricate an integrated circuit. One of the compelling advantages that plasma processing provides is the ability to drive material growth and material removal anisotropically to form high aspect ratio vertical features that are critical components in both logic and memory devices. In this talk, some of the recent efforts undertaken at NC State to advance these critical technologies will be presented. Specifically, three recent projects will be summarized: 1.) Molecular dynamic modelling of glancing angle ion interactions with high aspect ratio sidewalls, 2.) cathode design to control ion angle of incidence near the cathode edge, and 3.) development of a high aspect ratio sidewall charge measurement diagnostic to measure local fields inside one of these features. This work has been supported through grants from the US Department of Energy and Samsung Electronics as well as through continued support from the State of North Carolina.



Steven Shannon is Professor and Director of Graduate Programs for the where he directs research in and application. After 1999 he spent nine years as a member of the technical Santa Clara CA while also measurement of material interactions with materials. joined the faculty at NC Programs in 2020.